

**Notice of References Cited**

Application/Control No.

10/520,495

Applicant(s)/Patent Under  
Reexamination  
COSTA ET AL.

Examiner

NATHAN H. EMPIE

Art Unit

1792

Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-4,816,049	03-1989	Hata et al.	65/395
*	B	US-4,923,950	05-1990	Ravaine et al.	528/38
*	C	US-5,693,365	12-1997	Teranishi et al.	427/163.1
*	D	US-2002/0160153	10-2002	Minami et al.	428/156
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	H. Kim and H. Park "Surface Modified SiO <sub>2</sub> Xerogel Films from HMDS / Acetone for Intermetal Dielectrics" from 2000 International Microprocesses and Nanotechnology Conference, July 11-13, 2000 Tokyo, Japan pg 218-219.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
 Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.